

Notice of Allowability	Application No.	Applicant(s)	
	10/080,104	KOIKE ET AL.	
	Examiner	Art Unit	
	Fazli Erdem	2826	
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308. 1. This communication is responsive to Amendment filed on 11/21/2006.			
2. The allowed claim(s) is/are 23-37,51-57,61-65,69-82 and 84-86.			
3.			
Attachment(s) 1. ☐ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO/SB/08), Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5. Notice of Informal Pa 6. Interview Summary (Paper No./Mail Date 7. Examiner's Amendm 8. Examiner's Statemen 9. Other	PTO-413), e ent/Comment	wance
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Application/Control Number: 10/080,104

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DETAILED ACTION

Allowable Subject Matter

- 1. Claims 23-37, 51-57, 61-65, 69-82 and 84-86 allowed.
- The following is an examiner's statement of reasons for allowance: Prior art failed to 2. establish a method of producing a mask-making member, said member has a plurality of pattern formation regions in which mask circuit patterns are to be formed, and a supporting region in which any mask circuit pattern is not to be formed, said supporting region being provided for holding said plurality of pattern formation regions while separating said plurality of pattern formation regions from each other, said supporting region having first alignment marks used at the time of alignment with a mask made from said mask-making member for forming said mask circuit patterns thereon, second alignment marks being used at a time of alignment with a substrate to be exposed for forming circuit patterns thereon, said method comprising the step of: forming all of said first alignment marks and said second alignment marks of said mask-making member at one time, said first alignment marks being formed in such a manner that one or more of said first alignment marks are located in a portion of said supporting region around each of said plurality of pattern formation regions and said second alignment marks being formed in such a manner as to be all located in a portion of said supporting region outside an area formed by said plurality of said pattern formation regions, and the alignment with said mask-making member for forming said first alignment marks and said second alignment marks thereon at one time or dividing all of said first alignment marks and said second alignment marks to be formed on said mask into a plurality of groups each containing pluralities of said first alignment marks and said second alignment marks and sequentially forming said first alignment marks and said

second alignment marks on said mask by sequential exposure performed for each of said pluralities of groups.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Fazli Erdem whose telephone number is (571) 272-1914. The examiner can normally be reached on M - F 8:00 - 5:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Sue Purvis can be reached on (571) 272-1236. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

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February 1, 2007

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EVAN PERT PRIMARY EXAMINER